



PATENT  
8565D-7213 (81839.0077)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Teruaki FUKAMI

Serial No: 09/218,997

Filed: December 22, 1998

For: SILICON WAFER STORAGE  
WATER AND SILICON WAFER  
STORAGE METHOD

Art Unit: 1744

Examiner: Soubra, I.

7/A  
01.8  
1/11/01

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AMENDMENT

Box Non-Fee Amendment  
Asst. Commissioner for Patents  
Washington, D.C. 20231

Dear Sir:

In response to the Office Action dated October 5, 2000, please amend the  
above-identified application as follows:

IN THE CLAIMS:

Rewrite claims 1-20 as follows:

Sub B1 1. (Amended) [Storage] A storage water used for storage of a silicon wafer in water, wherein the storage water contains Cu at a concentration of 0.01 ppb or less.

A' 2. (Amended) [Storage] A storage water used for storage of a silicon wafer in water according to Claim 1, wherein the storage water contains a surfactant.

3. (Amended) A method of storing a silicon wafer in water, [wherein the silicon wafer is stored in] comprising the steps of preparing water or a chemical solution which does not cause degradation of oxide dielectric breakdown voltage due